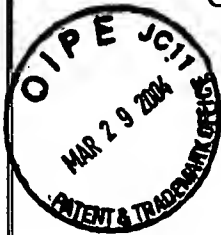


INFORMATION DISCLOSURE  
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(PTO-1449)

ATTY. DOCKET NO.  
005916  
USA/FPS/MMCS/MC

SERIAL NO.  
09/998,384

APPLICANT  
Young Joseph PAIK

FILING DATE  
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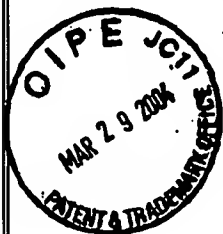
GROUP  
~~2812~~ 2823

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EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
K.N.	4,901,218	02/13/90	Cornwell			03/04/88
	5,427,878	06/27/95	Corliss			05/16/94
	5,761,065	06/02/98	Kittler et al.			03/30/95
	5,862,054	01/19/99	Li			02/20/97
	5,912,678	06/15/99	Saxena et al.			04/14/97
	5,926,690	07/20/99	Toprac et al.			05/28/97
	6,074,443	06/13/00	Venkatesh et al.			01/29/98
	6,111,634	08/29/00	Pecen et al.			05/28/97
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	6,442,496 B1	08/27/02	Pasady et al.			08/08/00
	6,486,492 B1	11/26/02	Su			11/20/00
	6,492,281 B1	12/10/02	Song et al.			09/22/00
	6,540,591 B1	04/01/03	Pasady et al.			04/18/01
	6,560,504 B1	05/06/03	Goodwin et al.			09/29/99
	6,590,179 B2	07/08/03	Tanaka et al.			02/26/01
	6,604,012 B1	08/05/03	Cho et al.			08/23/00
	6,618,692 B2	09/09/03	Takahashi et al.			02/26/01
	6,625,497 B2	09/23/03	Fairbairn et al.			07/10/01
✓ K.N.	6,640,151 B1	10/28/03	Somekh et al.			12/22/99
EXAMINER			DATE CONSIDERED			
K. Niemann			08/20/04			

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## FOREIGN PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
K.N.	0 397 924 A1 ✓	11/22/90	Europe			X	

## OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

K.N.	Rocha, Joao and Carlos Ramos. September 12, 1994. "Task Planning for Flexible and Agile Manufacturing Systems." <i>Intelligent Robots and Systems '94. Advanced Robotic Systems and the Real World, IROS '94. Proceedings of the IEEE/RSJ/GI International Conference on Munich, Germany 12-16 Sept. 1994.</i> New York, New York: IEEE. pp. 105-112.
✓	March 15, 2002. Office Action for U.S. Serial No. 09/469,227, filed December 22, 1999.
✓	March 29, 2002. Office Action for U.S. Serial No. 09/363,966, filed July 29, 1999.
✓	June 20, 2002. Office Action for U.S. Serial No. 09/619,044, filed July 19, 2000.
✓	September 26, 2002. Office Action for U.S. Serial No. 09/637,620, filed August 11, 2000.
✓	October 23, 2002. Office Action for U.S. Serial No. 09/469,227, filed December 22, 1999.
✓	December 17, 2002. Office Action for U.S. Serial No. 09/363,966, filed July 29, 1999.
✓	February 10, 2003. Office Action for U.S. Serial No. 09/619,044, filed July 19, 2000.
✓	April 9, 2003. Office Action for U.S. Serial No. 09/928,474, filed August 14, 2001.
✓	May 8, 2003. Office Action for U.S. Serial No. 09/637,620, filed August 11, 2000.
✓	June 18, 2003. Office Action for U.S. Serial No. 09/655,542, filed September 6, 2000.
✓	August 8, 2003. International Search Report for PCT/US03/08513.
✓	August 25, 2003. Office Action for U.S. Serial No. 10/100,184, filed March 19, 2002.
✓	September 15, 2003. Office Action for U.S. Serial No. 09/928,474, filed August 14, 2001.
✓	November 5, 2003. Office Action for U.S. Serial No. 10/172,977, filed June 18, 2002.
✓	December 1, 2003. Office Action for U.S. Serial No. 10/173,108, filed June 18, 2002.
✓	December 11, 2003. Office Action for U.S. Serial No. 09/943,383, filed August 31, 2001.
✓	December 16, 2003. International Search Report for PCT/US03/23964.
✓	January 20, 2004. Office Action for U.S. Serial No. 09/927,444, filed August 13, 2001.
✓	January 23, 2004. International Search Report for PCT/US02/24860.
K.N.	February 2, 2004. Office Action for U.S. Serial No. 09/363,966, filed July 29, 1999.

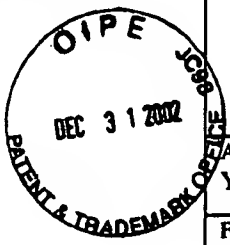

EXAMINER

J. K. Nguyen

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08/20/04

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<b>INFORMATION DISCLOSURE CITATION IN AN APPLICATION</b>  (PTO-1449)			ATTY. DOCKET NO. 005916 USA/FPS/MMCS/MC		SERIAL NO. 09/998,384	
			APPLICANT Young Joseph PAIK			
			FILING DATE November 30, 2001		GROUP <del>2812</del> 2823	
<b>U.S. PATENT DOCUMENTS</b>						
EXAMINER'S INITIALS	PUBLICATION / PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
K.N.	5,270,222	12/14/93	Moslehi			12/31/90
K.N.	5,375,064	12/20/94	Bollinger			12/02/93
K.N.	5,599,423	02/04/97	Parker et al.			06/30/95
K.N.	5,844,554	12/01/98	Geller et al.			09/17/96
<b>FOREIGN PATENT DOCUMENTS</b>						
EXAMINER'S INITIALS	PUBLICATION / PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation Yes No
K.N.	WO 95/34866	12/21/95	WO			X
↓	WO 98/45090	10/15/98	WO			X
↓	EP 0 881 040 A2	12/02/98	Europe			X
↓	WO 99/25520	05/27/99	WO			X
↓	WO 00/54325	09/14/00	WO			X
K.N.	EP 1 066 925 A2	01/10/01	Europe			X
K.N.	EP 1 092 505 A2	04/18/01	Europe			X
<b>OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)</b>						
K.N.	Hu, Albert, Kevin Nguyen, Steve Wong, Xiuhua Zhang, Emanuel Sachs, and Peter Renteln. 1993. "Concurrent Deployment of Run by Run Controller Using SCC Framework." IEEE/SEMI International Semiconductor Manufacturing Science Symposium. pp. 126-132.					
↓	Hu, Albert, He Du, Steve Wong, Peter Renteln, and Emanuel Sachs. 1994. "Application of Run by Run Controller to the Chemical-Mechanical Planarization Process." IEEE/CPMT International Electronics Manufacturing Technology Symposium. pp. 371-378.					
↓	Smith, Taber, Duane Boning, James Moyne, Arnon Hurwitz, and John Curry. June 1996. "Compensating for CMP Pad Wear Using Run by Run Feedback Control." Proceedings of the Thirteenth International VLSI Multilevel Interconnection Conference. pp. 437-439.					
↓	Suzuki, Junichi and Yoshikazu Yamamoto. 1998. "Toward the Interoperable Software Design Models: Quartet of UML, XML, DOM and CORBA." Proceedings IEEE International Software Engineering Standards Symposium. pp. 1-10.					
K.N.	Klein, Bruce. June 1999. "Application Development: XML Makes Object Models More Useful." Informationweek. pp. 1A-6A.					
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EXAMINER'S INITIALS	PUBLICATION / PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
K.N.	5,889,991	03/30/99	Consolatti et al.			12/06/96
	6,183,345 B1	02/06/01	Kamono et al.			03/20/98
	6,253,366 B1	06/26/01	Mutschler, III			03/31/99
K.N.	6,298,470 B1	10/02/01	Breiner et al.			04/15/99

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EXAMINER'S INITIALS	PUBLICATION / PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
K.N.	WO 01/52055 A3	07/19/01	WO			X	
	WO 01/57823 A2	08/09/01	WO			X	
	EP 1 182 526 A2	02/27/02	Europe			X	
	WO 02/17150 A1	02/28/02	WO			X	
K.N.	WO 02/33737 A2	04/25/02	WO			X	

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K.N.	Chemali, Chadi El, James Moyné, Kareemullah Khan, Rock Nadeau, Paul Smith, John Colt, Jonathan Chapple-Sokol, and Tarun Parikh. July/August 2000. "Multizone Uniformity Control of a Chemical Mechanical Polishing Process Utilizing a Pre- and Postmeasurement Strategy." J. Vac. Sci. Technol. A, Vol. 18(4). pp. 1287-1296. American Vacuum Society.
K.N.	Jensen, Alan, Peter Renteln, Stephen Jew, Chris Raeder, and Patrick Cheung. June 2001. "Empirical-Based Modeling for Control of CMP Removal Uniformity." Solid State Technology, Vol. 44, No. 6, pp. 101-102, 104, 106. Cowan Publ. Corp.: Washington, D.C.
K.N.	Sarfaty, Moshe, Arulkumar Shanmugasundram, Alexander Schwarm, Joseph Paik, Jimin Zhang, Rong Pan, Martin J. Seamons, Howard Li, Raymond Hung, and Suketu Parikh. April/May 2002. "Advance Process Control Solutions for Semiconductor Manufacturing." IEEE/SEMI Advanced Semiconductor Manufacturing Conference. pp. 101-106.
K.N.	October 4, 2002. International Search Report from PCT/US01/22833.
K.N.	October 23, 2002. International Search Report from PCT/US01/27406.
K.N.	November 7, 2002. International Search Report from PCT/US02/19061.
K.N.	November 11, 2002. International Search Report from PCT/US02/19117.
K.N.	November 12, 2002. International Search Report from PCT/US02/19063.
EXAMINER	DATE CONSIDERED
<i>[Signature]</i>	08/20/04

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**U.S. PATENT DOCUMENTS**

EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
K.N.	4,796,194	01/03/89	Atherton			08/20/86
	5,089,970	02/18/92	Lee et al.			10/05/89
	5,108,570	04/28/92	Wang			03/30/90
	5,220,517	06/15/93	Sierk et al.			08/31/90
	5,236,868	08/17/93	Nulman			04/20/90
	5,260,868	11/09/93	Gupta et al.			10/15/91
	5,295,242	03/15/94	Mashruwala et al.			11/02/90
	5,309,221	05/03/94	Fischer et al.			12/31/91
	5,329,463	07/12/94	Sierk et al.			01/13/93
	5,367,624	11/22/94	Cooper			06/11/93
	5,398,336	03/14/95	Tantry et al.			06/16/93
	5,402,367	03/28/95	Sullivan et al.			07/19/93
	5,408,405	04/18/95	Mozumder et al.			09/20/93
K.N.	5,410,473	04/25/95	Kaneko et al.			12/16/92

**FOREIGN PATENT DOCUMENTS**

EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
K.N.	01-283934	11/15/89	Japan			X	
K.N.	2,050,247	08/29/91	Canada			X	

**OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)**

K.N.	Dishon, G., D. Eylon, M. Finarov, and A. Shulman. "Dielectric CMP Advanced Process Control Based on Integrated Monitoring." Ltd. Rehoveth, Israel: Nova Measuring Instruments.
K.N.	Runyan, W. R., and K. E. Bean. 1990. "Semiconductor Integrated Circuit Processing Technology." pg. 48. Reading, Massachusetts: Addison-Wesley Publishing Company.


EXAMINER

DATE CONSIDERED



*Khien Nguyen*

08/20/04

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				APPLICANT Young Joseph PAIK			
				FILING DATE November 30, 2001		GROUP <del>2812</del> 2823	
<b>U.S. PATENT DOCUMENTS</b>							
EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE	
K.N.	5,490,097	02/06/96	Swenson et al.			08/06/93	
	5,495,417	02/27/96	Fuduka et al.			03/16/93	
	5,497,316	03/05/96	Sierk et al.			04/04/95	
	5,503,707	04/02/96	Maung et al.			09/22/93	
	5,508,947	04/16/96	Sierk et al.			05/13/94	
	5,629,216	05/13/97	Wijaranakula et al.			02/27/96	
	5,657,254	08/12/97	Sierk et al.			04/15/96	
	5,661,669	08/26/97	Mozumder et al.			06/07/95	
	5,694,325	12/02/97	Fukuda et al.			11/22/95	
	5,698,989	12/16/97	Nulman			09/13/96	
	5,719,495	02/17/98	Moslehi			06/05/96	
	5,740,429	04/14/98	Wang et al.			07/07/95	
	5,751,582	05/12/98	Saxena et al.			09/24/96	
	5,754,297	05/19/98	Nulman			04/14/97	
K.N.	5,764,543	06/09/98	Kennedy			06/16/95	
<b>FOREIGN PATENT DOCUMENTS</b>							
EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
K.N.	2,165,847	08/29/91	Canada			X	
K.N.	2,194,855	08/29/91	Canada			X	
<b>OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)</b>							
K.N.	Zorich, Robert. 1991. <i>Handbook of Quality Integrated Circuit Manufacturing</i> . pp. 464-498 San Diego, California: Academic Press, Inc.						
K.N.	Rampalli, Prasad, Arakere Ramesh, and Nimish Shah. 1991. <i>CEPT—A Computer-Aided Manufacturing Application for Managing Equipment Reliability and Availability in the Semiconductor Industry</i> . New York, New York: IEEE.						
EXAMINER  <i>Khiamnguyen</i>				DATE CONSIDERED  08/20/04			

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				APPLICANT Young Joseph PAIK			
				FILING DATE November 30, 2001		GROUP <del>2812</del> 2823	
<b>U.S. PATENT DOCUMENTS</b>							
EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE	
K.N.	5,808,303	09/15/98	Schlagheck et al.			01/29/97	
↓	5,838,595	11/17/98	Sullivan et al.			11/25/96	
↓	5,883,437	03/16/99	Maruyama et al.			12/28/95	
↓	5,910,011	06/08/99	Cruse			05/12/97	
K.N.	6,054,379	04/25/00	Yau et al.			02/11/98	
<b>FOREIGN PATENT DOCUMENTS</b>							
EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation Yes No	
K.N.	05-151231	06/18/93	Japan				X
↓	05-216896	08/27/93	Japan				X
↓	05-266029	10/15/93	Japan				X
↓	06-110894	04/22/94	Japan				X
↓	06-176994	06/24/94	Japan				X
↓	06-252236	09/09/94	Japan				X
↓	06-260380	09/16/94	Japan				X
↓	08-149583	06/07/96	Japan			X	
↓	09-34535	02/07/97	Japan			X	
↓	EP 0877308 A2	11/11/98	Europe			X	
↓	11-67853	03/09/99	Japan			X	
K.N.	1072967A3	11/21/01	Europe			X	
<b>OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)</b>							
K.N.	Moyne, James R., Nauman Chaudhry, and Roland Telfeyan. 1995. "Adaptive Extensions to a Multi-Branch Run-to-Run Controller for Plasma Etching." <i>Journal of Vacuum Science and Technology</i> . Ann Arbor, Michigan: University of Michigan Display Technology Manufacturing Center.						
K.N.	Moyne, James, Roland Telfeyan, Arnon Hurwitz, and John Taylor. August 1995. "A Process-Independent Run-to-Run Controller and Its Application to Chemical-Mechanical Planarization." <i>SEMI/IEEE Advanced Semiconductor Manufacturing Conference and Workshop</i> . Ann Arbor, Michigan: The University of Michigan, Electrical Engineering & Computer Science Center for Display Technology & Manufacturing.						
EXAMINER  				DATE CONSIDERED  08/20/04			

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November 30, 2001

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**U.S. PATENT DOCUMENTS**

EXAMINER'S INITIALS	PATENT APPLICATION NO.	FILING DATE	NAME	TITLE	CLASS	SUB- CLASS
K.N.	09/363,966	07/29/99	Arackaparambil et al.	Computer Integrated Manufacturing Techniques		
K.N.	09/469,227	12/22/99	Somekh et al.	Multi-Tool Control System, Method and Medium		
K.N.	09/619,044	07/19/00	Yuan	System and Method of Exporting or Importing Object Data in a Manufacturing Execution System		
K.N.	09/637,620	08/11/00	Chi et al.	Generic Interface Builder		
K.N.	09/656,031	09/06/00	Chi et al.	Dispatching Component for Associating Manufacturing Facility Service Requestors with Service Providers		

**FOREIGN PATENT DOCUMENTS**

EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUB- CLASS	Translation	
						Yes	No
/	/	/	/	/	/	/	/

**OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)**

K.N.	Zhou, Zhen-Hong and Rafael Reif. August 1995. "Epi-Film Thickness Measurements Using Emission Fourier Transform Infrared Spectroscopy—Part II: Real-Time <i>in Situ</i> Process Monitoring and Control." IEEE Transactions on Semiconductor Manufacturing, Vol. 8, No. 3.
K.N.	Telfeyan, Roland, James Moyne, Nauman Chaudhry, James Pugmire, Scott Shellman, Duane Boning, William Moyne, Arnon Hurwitz, and John Taylor. October 1995. "A Multi-Level Approach to the Control of a Chemical-Mechanical Planarization Process." Minneapolis, Minnesota: 42 <sup>nd</sup> National Symposium of the American Vacuum Society.
K.N.	Chang, E., B. Stine, T. Maung, R. Divecha, D. Boning, J. Chung, K. Chang, G. Ray, D. Bradbury, O. S. Nakagawa, S. Oh, and D. Bartelink. December 1995. "Using a Statistical Metrology Framework to Identify Systematic and Random Sources of Die- and Wafer-level ILD Thickness Variation in CMP Processes." Washington, D.C.: International Electron Devices Meeting.

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*[Signature]*

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## U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT APPLICATION NO.	FILING DATE	NAME	TITLE	CLASS	SUB-CLASS
K.N.	09/655,542	09/06/00	Yuan	System, Method and Medium for Defining Palettes to Transform an Application Program Interface for a Service		
	09/725,908	11/30/00	Chi et al.	Dynamic Subject Information Generation in Message Services of Distributed Object Systems		
	09/800,980	03/08/01	Hawkins et al.	Dynamic and Extensible Task Guide		
	09/811,667	03/20/01	Yuan et al.	Fault Tolerant and Automated Computer Software Workflow		
	09/927,444	08/13/01	Ward et al.	Dynamic Control of Wafer Processing Paths in Semiconductor Manufacturing Processes		
K.N.	09/928,473	08/13/01	Koh	Tool Services Layer for Providing Tool Service Functions in Conjunction with Tool Functions		

## FOREIGN PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUB-CLASS	Translation
						Yes No

## OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

K.N.	Dishon, G., M. Finarov, R. Kipper, J.W. Curry, T. Schraub, D. Trojan, 4 <sup>th</sup> Stambaugh, Y. Li and J. Ben-Jacob. February 1996. "On-Line Integrated Metrology for CMP Processing." Santa Clara, California: VMIC Speciality Conferences, 1 <sup>st</sup> International CMP Planarization Conference.
	Smith, Taber, Duane Boning, James Moyne, Arnon Hurwitz, and John Curry. June 1996. "Compensating for CMP Pad Wear Using Run by Run Feedback Control." Santa Clara, California: VLSI Multilevel Interconnect Conference.
	Boning, Duane, William Moyne, Taber Smith, James Moyne, Roland Telfeyan, Arnon Hurwitz, Scott Shellman, and John Taylor. October 1996. "Run by Run Control of Chemical-Mechanical Polishing." <i>IEEE Trans. CPMT (C)</i> , Vol. 19, No. 4, pp. 307-314.
K.N.	SEMI. [1986] 1996. "Standard for Definition and Measurement of Equipment Reliability, Availability, and Maintainability (RAM)." SEMI E10-96.

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**09/998,384**

**FILING DATE**  
**November 30, 2001**

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~~2812~~ 2823



EXAMINER'S INITIALS	PATENT APPLICATION NO.	FILING DATE	NAME	TITLE	CLASS	SUB-CLASS
K.N.	09/928,474	08/14/01	Krishnamurthy et al.	Experiment Management System, Method and Medium		
↓	09/943,383	08/31/01	Shanmugasundram et al.	In Situ Sensor Based Control of Semiconductor Processing Procedure		
↓ K.N.	09/943,955	08/31/01	Shanmugasundram et al.	Feedback Control of a Chemical Mechanical Polishing Device Providing Manipulation of Removal Rate Profiles		

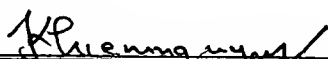
EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUB- CLASS	Translation	
						Yes	No

K.N.	Van Zant, Peter. 1997. <i>Microchip Fabrication: A Practical Guide to Semiconductor Processing</i> . Third Edition, pp. 472-478. New York, New York: McGraw-Hill.
	Campbell, W. Jarrett, and Anthony J. Toprac. February 11-12, 1998. "Run-to-Run Control in Microelectronics Manufacturing." Advanced Micro Devices, TWMCC.
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	Chemali, Chadi El, James Moyne, Kareemullah Khan, Rock Nadeau, Paul Smith, John Colt, Jonathan Chapple-Sokol, and Tarun Parikh. November 1998. "Multizone Uniformity Control of a CMP Process Utilizing a Pre and Post-Measurement Strategy." Seattle, Washington: SEMETECH Symposium.
	Consilium. 1998. <i>FAB300™</i> . Mountain View, California: Consilium, Inc.
✓ K.N.	Khan, Kareemullah, Victor Solakhain, Anthony Ricci, Tier Gu, and James Moyne. 1998. "Run-to-Run Control of ITO Deposition Process." Ann Arbor, Michigan.




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<b>INFORMATION DISCLOSURE CITATION IN AN APPLICATION (PTO-1449)</b>				ATTY. DOCKET NO. 005916 USA/FPS/MMCS/MC		SERIAL NO. 09/998,384	
				APPLICANT Young Joseph PAIK			
				FILING DATE November 30, 2001		GROUP <del>2812</del> 2823	
<b>U.S. PATENT DOCUMENTS</b>							
EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE	
K.N.	3,767,900	10/23/73	Chao et al.			06/23/71	
	3,920,965	11/18/75	Sohrwardy			03/04/74	
	4,368,510	01/11/83	Anderson			10/20/80	
	4,616,308	10/07/86	Morshedi et al.			12/02/85	
	4,663,703	05/05/87	Axelby et al.			10/02/85	
	5,347,446	09/13/94	Iino et al.			02/10/92	
	5,519,605	05/21/96	Cawlfild			10/24/94	
	6,128,016	10/03/00	Coelho et al.			12/20/96	
	6,219,711	04/17/01	Chari			10/01/97	
	6,249,712	06/19/01	Boiquaye			09/25/96	
	6,278,899	08/21/01	Piche et al.			10/06/98	
	2001/0039462	11/08/01	Mendez et al.			04/02/01	
	2001/0040997	11/15/01	Tsap et al.			05/15/01	
	2002/0128805	09/12/02	Goldman et al.			12/26/00	
	<b>FOREIGN PATENT DOCUMENTS</b>						
EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
K.N.	EP 1 067 757	01/10/01	Europe			X	
K.N.	WO 01/33277	05/10/01	WO			X	
K.N.	WO 02/31613 A2	04/18/02	WO			X	
K.N.	WO 02/31613 A3	04/18/02	WO			X	
<b>OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)</b>							
K.N.	Levine, Martin D. 1985. <i>Vision in Man and Machine</i> . New York: McGraw-Hill, Inc. pp. ix-xii, 1-58.						
K.N.	Pilu, Maurizio. September 2001. "Undoing Page Curl Distortion Using Applicable Surfaces." <i>IEEE International Conference on Image Processing</i> . Thessalonica, Greece.						
	23 May 2003. Written Opinion for PCT/US01/24910.						
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				08/20/04			

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<b>U.S. PATENT DOCUMENTS</b>							
EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE	
K.N.	4,207,520	06/10/80	Flora et al.			04/06/78	
	4,209,744	06/24/80	Gerasimov et al.			03/27/78	
	4,609,870	09/02/86	Lale et al.			09/13/84	
	4,755,753	07/05/88	Chern			07/23/86	
	5,427,878	06/27/95	Corliss			05/16/94	
	5,534,289	07/09/96	Bilder et al.			01/03/95	
	5,867,389	02/02/99	Hamada et al.			11/26/96	
	6,041,263	03/21/00	Boston et al.			10/01/97	
	6,077,412	06/20/00	Ting et al.			10/30/98	
	6,271,670	08/07/01	Caffey			02/08/99	
	6,400,162	06/04/02	Mallory et al.			07/21/00	
	US 2002/0077031	06/20/02	Johansson et al.			07/06/01	
	6,442,496	08/27/02	Pasadyne et al.			08/08/00	
	6,563,308	05/13/03	Nagano et al.			03/27/01	
K.N.	6,587,744	07/01/03	Stoddard et al.			06/20/00	
<b>FOREIGN PATENT DOCUMENTS</b>							
EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
K.N.	WO 01/11679	02/15/01	WIPO			X	
K.N.	WO 01/080306	10/25/01	WIPO			X	
<b>OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)</b>							
K.N.	Miller, G. L., D. A. H. Robinson, and J. D. Wiley. July 1976. "Contactless measurement of semiconductor conductivity by radio frequency-free-carrier power absorption." <i>Rev. Sci. Instrum.</i> , Volume 47, No. 7. pp. 799 - 805.						
K.N.	1999. "Contactless Bulk Resistivity/Sheet Resistance Measurement and Mapping Systems." <a href="http://www.Lehighton.com/fabtech1/index.html">www.Lehighton.com/fabtech1/index.html</a> .						
K.N.	2000. "Microsense II Capacitance Gaging System." <a href="http://www.adetech.com">www.adetech.com</a> .						
EXAMINER				DATE CONSIDERED			
							

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				FILING DATE November 30, 2001		GROUP 2812 2823	
<b>FOREIGN PATENT DOCUMENTS</b>							
EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
<b>OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)</b>							
K.N.							El Chemali, Chadi et al. July/August 2000. "Multizone uniformity control of a chemical mechanical polishing process utilizing a pre- and postmeasurement strategy." <i>J. Vac. Sci. Technol.</i> Volume 18, No. 4. pp. 1287 - 1296.
							March 5, 2001. "KLA-Tencor Introduces First Production-worthy Copper CMP In-situ Film Thickness and End-point Control System." <a href="http://www.kla-tencor.com/j/servlet/NewsItem?newsItemID=74">http://www.kla-tencor.com/j/servlet/NewsItem?newsItemID=74</a> .
							2002. "Microsense II - 5810: Non-Contact Capacitance Gaging Module." <a href="http://www.adetech.com">www.adetech.com</a> .
							08 August 2003. PCT International Search Report from PCT/US03/08513.
							14 October 2003. PCT International Search Report from PCT/US02/21942.
							20 October 2003. PCT International Search Report from PCT/US02/19116.
							23 October 2003. PCT International Preliminary Examination Report from PCT/US01/24910.
							"NanoMapper wafer nanotopography measurement by ADE Phase Shift." <a href="http://www.phase-shift.com/nanomap.shtml">http://www.phase-shift.com/nanomap.shtml</a> .
							"Wafer flatness measurement of advanced wafers." <a href="http://www.phase-shift.com/wafer-flatness.shtml">http://www.phase-shift.com/wafer-flatness.shtml</a> .
							"ADE Technologies, Inc. - 6360." <a href="http://www.adetech.com/6360.shtml">http://www.adetech.com/6360.shtml</a> .
							"3D optical profilometer MicroXAM by ADE Phase Shift." <a href="http://www.phase-shift.com/microxam.shtml">http://www.phase-shift.com/microxam.shtml</a> .
K.N.							"NanoMapper FA factory automation wafer nanotopography measurement." <a href="http://www.phase-shift.com/nanomapperfa.shtml">http://www.phase-shift.com/nanomapperfa.shtml</a> .
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APPLICANT  
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FILING DATE  
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## U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
K.N.	5,655,951	08/12/97	Meikle et al.			09/29/95
↓	5,823,854	10/20/98	Chen			05/28/96
↓	5,859,975	01/12/99	Brewer et al.			08/09/96
K.N.	6,389,491	05/14/02	Jacobson et al.			03/23/99

## FOREIGN PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
K.N.	2 347 885 A	09/20/00	GB			X	
K.N.	WO 01/15865 A1	03/08/01	WO			X	

## OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

K.N.	July 23, 2002. Communication Pursuant to Article 96(2) EPC for European Patent Application No. 00 115 577.9.
K.N.	October 15, 2002. International Search Report prepared by the European Patent Office for PCT/US02/19062.
EXAMINER	DATE CONSIDERED
<i>K.N. [Signature]</i>	<i>08/20/04</i>

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5916/FET/FET/DV

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09/998,384

APPLICANT  
Young Joseph PAIK

FILING DATE  
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GROUP  
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## U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
K.N.	4,698,766	10/06/87	Entwistle et al.			05/17/85
	4,967,381	10/30/90	Lane et al.			07/06/89
	5,208,765	05/04/93	Turnbull			07/20/90
	5,226,118	07/06/93	Baker et al.			01/29/91
	5,231,585	07/27/93	Kobayashi et al.			06/20/90
	5,420,796	05/30/95	Weling et al.			12/23/93
	5,469,361	11/21/95	Moyne			06/06/94
	5,525,808	06/11/96	Irie et al.			12/20/94
	5,586,039	12/17/96	Hirsch et al.			02/27/95
	5,603,707	02/18/97	Trombetta et al.			11/28/95
	5,664,987	09/09/97	Renteln			09/04/96
	5,812,407	09/22/98	Sato et al.			08/12/97
	5,828,778	10/27/98	Hagi et al.			06/12/96
K.N.	5,832,224	11/03/98	Fehskens et al.			06/14/96

## FOREIGN PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
K.N.	61-171147	08/01/86	Japan				X
	6-184434	07/05/94	Japan				X
	0 621 522 A2	10/26/94	Europe			X	
	8-50161	02/20/96	Japan				X
K.N.	8-304023	11/22/96	Japan				X

## OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

K.N.	February 1984. "Method and Apparatus of in Situ Measurement and Overlay Error Analysis for Correcting Step and Repeat Lithographic Cameras." <i>IBM Technical Disclosure Bulletin</i> , pp. 4855-4859.
K.N.	October 1984. "Method to Characterize the Stability of a Step and Repeat Lithographic System." <i>IBM Technical Disclosure Bulletin</i> , pp. 2857-2860.

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*K. R. ...*

08/20/04

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## U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
K.N.	5,859,964	01/12/99	Wang et al.			10/25/96
	5,863,807	01/26/99	Jang et al.			03/15/96
	5,870,306	02/09/99	Harada			06/13/97
	5,903,455	05/11/99	Sharpe, Jr. et al.			12/12/96
	5,916,016	06/29/99	Bothra			10/23/97
	5,923,553	07/13/99	Yi			10/05/96
	5,930,138	07/27/99	Lin et al.			09/10/97
	5,940,300	08/17/99	Ozaki			05/08/97
	5,960,214	09/28/99	Sharpe, Jr. et al.			12/04/96
	5,963,881	10/05/99	Kahn et al.			10/20/97
	5,982,920	11/09/99	Tobin, Jr. et al.			01/08/97
	6,041,270	03/21/00	Steffan et al.			12/05/97
	6,078,845	06/20/00	Friedman			11/25/96
	6,112,130	08/29/00	Fukuda et al.			10/01/97
K.N.	6,148,246	11/14/00	Kawazome			06/10/98

## FOREIGN PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
K.N.	0 747 795 A2	12/11/96	Europe			X	
	10-173029	06/26/98	Japan				X
	0 895 145 A1	02/03/99	Europe			X	
K.N.	11-126816	05/11/99	Japan				X

## OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

K.N.	Schmid, Hans Albrecht. 1995. "Creating the Architecture of a Manufacturing Framework by Design Patterns." Austin, Texas: OOPSLA.
K.N.	Baliga, John. July 1999. "Advanced Process Control: Soon to be a Must." Cahners Semiconductor International. <a href="http://www.semiconductor.net/semiconductor/issues/issues/1999/jul99/docs/feature1.asp">www.semiconductor.net/semiconductor/issues/issues/1999/jul99/docs/feature1.asp</a>
EXAMINER	DATE CONSIDERED
<i>[Signature]</i>	08/20/04

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INFORMATION DISCLOSURE  
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ATTY. DOCKET NO.  
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GROUP:  
~~2812~~ 2823

## U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
K.N.	6,175,777	01/16/01	Kim			01/16/98
	6,178,390	01/23/01	Jun			09/08/98
	6,185,324	02/06/01	Ishihara et al.			01/31/95
	6,192,291	02/20/01	Kwon			10/08/98
	6,197,604	03/06/01	Miller et al.			10/01/98
	6,211,094	04/03/01	Jun et al.			08/23/99
	6,226,792	05/01/01	Goiffon et al.			10/14/98
	6,230,069	05/08/01	Campbell et al.			06/26/98
	6,236,903	05/22/01	Kim et al.			09/25/98
K.N.	6,240,330	05/29/01	Kurtzberg et al.			05/28/97

## FOREIGN PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
K.N.	11-135601	05/21/99	Japan				X
	WO 00/05759	02/03/00	WO			X	
K.N.	WO 00/35063	06/15/00	WO			X	

## OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

K.N.	July 5, 2001. "Motorola and Advanced Micro Devices Buy ObjectSpace Catalyst Advanced Process Control Product for Five Wafer Fabs." Semiconductor FABTECH. <a href="http://www.semiconductorfabtech.com/industry.news/9907/20.07.shtml">www.semiconductorfabtech.com/industry.news/9907/20.07.shtml</a>
	October 15, 2001. Search Report prepared by the Austrian Patent Office for Singapore Patent Application No. 200004286-1.
	Johnson, Bob. June 10, 2002. "Advanced Process Control Key to Moore's Law." Gartner, Inc.
	July 9, 2002. International Search Report prepared by the European Patent Office for PCT/US01/24910.
	July 29, 2002. International Search Report prepared by the European Patent Office for PCT/US01/27407.
K.N.	Sonderman, Thomas. 2002. "APC as a Competitive Manufacturing Technology: AMD's Vision for 300mm." AEC/APC.
EXAMINER	DATE CONSIDERED
K.P. Henningsen	08/20/04

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K.N.	3,205,485	09/07/65	Noltingk			10/21/60
	3,229,198	01/11/66	Libby			09/28/62
	4,000,458	12/28/76	Miller et al.			08/21/75
	4,302,721	11/24/81	Urbanek et al.			05/15/79
	4,750,141	06/07/88	Judell et al.			11/26/85
	4,757,259	07/12/88	Charpentier			11/05/86
	4,938,600	07/03/90	Into			02/09/89
	5,283,141	02/01/94	Yoon et al.			03/05/92
	5,338,630	08/16/94	Yoon et al.			11/18/93
	5,485,082	01/16/96	Wisspeintner et al.			04/05/90
	5,497,381	03/05/96	O'Donoghue et al.			06/01/95
	5,511,005	04/23/96	Abbe et al.			02/16/94
	5,519,605	05/21/96	Cawlfeld			10/24/94
	5,526,293	06/11/96	Mozumder et al.			12/17/93
	5,541,510	06/30/96	Danielson			04/06/95
	5,546,312	08/13/96	Mozumder et al.			02/24/94
	5,553,195	09/03/96	Meijer			09/29/94
	5,602,492	02/11/97	Cresswell et al.			04/28/94
	5,617,023	04/01/97	Skalski			02/02/95
	5,627,083	05/06/97	Tounai			05/12/95
	5,642,296	06/24/97	Saxena			07/29/93
	5,646,870	07/08/97	Krivokapic et al.			02/13/95
	5,649,169	07/15/97	Berezin et al.			06/20/95
	5,654,903	08/05/97	Reitman et al.			11/07/95
	5,663,797	09/02/97	Sandhu			05/16/96
✓	5,665,199	09/09/97	Sahota et al.			06/23/95
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	5,719,796	02/17/98	Chen			12/04/95
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SERIAL NO.  
09/998,384

APPLICANT  
Young Joseph PAIK

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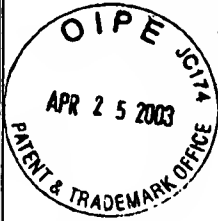
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*K. Phienmngues*

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						Yes	No
K.N.	61-66104	04/04/86	Japan			X	
	3-202710	09/04/91	Japan			X	
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	0 869 652	10/07/98	Europe			X	
	WO 99/09371	02/25/99	WIPO			X	
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✓	WO 00/00874	01/06/00	WIPO			X	
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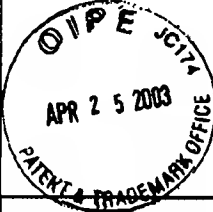

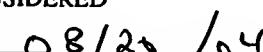
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				APPLICANT Young Joseph PAIK			
				FILING DATE November 30, 2001		GROUP <del>2812</del> 2823	
<b>FOREIGN PATENT DOCUMENTS</b>							
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						Yes	No
K.N.	1 071 128	01/24/01	Europe			X	
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K. H. Cunningham		08/20/04	

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<b>INFORMATION DISCLOSURE CITATION IN AN APPLICATION (PTO-1449)</b>		<b>ATTY. DOCKET NO.</b> 005916 USA/FPS/MMCS/MC	<b>SERIAL NO.</b> 09/998,384
		<b>APPLICANT</b> Young Joseph PAIK	
		<b>FILING DATE</b> November 30, 2001	<b>GROUP</b> <del>2812</del> 2823
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